



HOLDER OF PHOTOMASK

BACKGROUND OF THE INVENTION

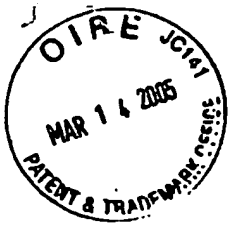
1. Field of the Invention:

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The present invention provides an apparatus comprising a photomask holder for holding a photomask, which is placed in the transfer box and is suitable for photolithography process. The photomask is disposed on the long cambered surface of the protrusion disposed in the photomask holder so that the friction between the protrusions and the Chromium (Cr) deposition formed on the bottom surface of the photomask can be effectively prevented. Thus, generation of particulates can be effectively prevented.

2. Description of the Related Art:

Heretofore, a conventional holder 10 of a photomask 201 (as illustrated in Fig. 1 & 2) is placed in a base 20 of a transfer box. The holder 10 is U-shaped and comprises pluralities of falciform members 101 and protrusions 102. The holder 10 is made of plastic material and is formed as a one-piece structure via injection molding process, and the protrusion 102 is adopted to support the photomask 201. As the surface contact area of the protrusion 102 with the photomask 201 is rather large and since the protrusion 102 is made of a plastic material, the protrusion 102 is not strong enough to resist friction with the photomask 201.



HOLDER OF PHOTOMASK

BACKGROUND OF THE INVENTION

1. Field of the Invention:

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The present invention provides an apparatus comprising a photomask ~~of holder of photomask~~ for holding a the photomask, which is placed in the transfer box and ~~to be exposed by projecting optical light during~~ is suitable for photolithography process of manufacturing semiconductor. The photomask is disposed on the ~~By means of the long cambered surface of the protrusion disposed~~ in the photomask holder to uphold photo mask, it prevents so that the friction between the protrusions and the protrusion from ~~friction that with~~ the Chromium (Cr) deposition formed on the bottom surface of the photomask can be effectively prevented. ~~therein in consequence of not creating any dust particle.~~ Thus, generation of particulates can be effectively prevented.

2. Description of the Related Art:

Heretofore, a conventional holder 10 of a the photomask 201 (as illustrated in Fig. 1 & 2) is placed in a base 20 of a the transfer box. The holder 10 is U-shaped and comprises pluralities of ~~with several~~ falciform members 101 and ~~several~~ protrusions 102. The holder 10 is made of ~~plasties in~~ plastic material and is formed as a one-piece structure via injection molding process ~~by eject forming~~, and the protrusion 102 is